



Addendum

Addendum: Zhang, C., et al. Pulsed Laser-Assisted Helium Ion Nanomachining of Monolayer Graphene—Direct-Write Kirigami Patterns. *Nanomaterials* 2019, 9, 1394

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The authors wish to make the following corrections to this paper [1]:

The funding section needs to be corrected. The updated information is included below:

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This addendum does not cause any changes to the results or conclusions in the original published paper.

The authors would like to apologize for any inconvenience caused to the readers by these changes.

Reference

1. Zhang, C.; Dyck, O.; Garfinkel, D.A.; Stanford, M.G.; Belianinov, A.A.; Fowlkes, J.D.; Jesse, S.; Rack, P.D. Pulsed Laser-Assisted Helium Ion Nanomachining of Monolayer Graphene—Direct-Write Kirigami Patterns. *Nanomaterials* **2019**, *9*, 1394. [[CrossRef](#)] [[PubMed](#)]



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